

AMENDMENTS TO THE CLAIMS

This listing of claims replaces all prior versions, and listing of claims in the application.

Listing of the Claims:

1. (Currently Amended) An apparatus for etching a glass substrate, comprising:
an etching bath containing an etchant;
a holder for supporting said glass substrate in the etching bath;
an ultrasonic oscillator generating ultrasonic vibration on ~~[[multiple]]~~ opposite surfaces of said substrate;
wherein the ultrasonic oscillator is located ~~in the interior~~ on two opposite sides of the etching bath; and
an indicator displaying a temperature of the etching bath.
2. (Original) The apparatus for etching a glass substrate of Claim 1, wherein said etchant comprises hydrofluoric acid.
3. (Original) The apparatus for etching a glass substrate of Claim 1, wherein said holder comprises acid-resistant material.
4. (Original) The apparatus for etching a glass substrate of Claim 3, wherein said acid resistant material comprises polytetrafluoroethylene.

5. (Original) The apparatus for etching a glass substrate of Claim 1, further comprising a thermometer for measuring the temperature of the etchant.

6. (Original) The apparatus for etching a glass substrate of Claim 1, further comprising a thermostat for signaling a specific temperature rise of said etchant.

7. (Original) The apparatus for etching a glass substrate of Claim 1, wherein said holder supports a plurality of glass substrates.

Claims 8 and 9 (Canceled).

10. (Original) The apparatus for etching a glass substrate of Claim 1, wherein said holder is located in an interior of said etching bath.

11. (Currently Amended) An apparatus for etching a glass substrate, comprising:
an etching bath filled with an etchant;
a holder for supporting said glass substrate in the etching bath;
an ultrasonic oscillator generating ultrasonic vibration on [[a]] opposite surfaces of said substrate, wherein the ultrasonic vibration emanates from bottom and side surfaces of the etching bath and wherein the ultrasonic oscillator is located in the interior of the etching bath; and
an indicator displaying a temperature of the etching bath.

12. (Previously Presented) The apparatus for etching a glass substrate of Claim 21, further comprising a control unit for receiving a temperature indicating signal from said temperature

sensor and generating an etching termination signal when the temperature signal indicates an etching termination temperature.

13. (Original) The apparatus for etching a glass substrate of Claim 12, wherein said control unit determines said etching termination temperature from said temperature indicating signal.

14. (Original) The apparatus for etching a glass substrate of Claim 11, wherein said etchant comprises hydrofluoric acid.

15. (Original) The apparatus for etching a glass substrate of Claim 11, wherein said holder comprises acid resistant material.

16. (Original) The apparatus for etching a glass substrate of Claim 15, wherein said acid resistant material comprises polytetrafluoroethylene.

17. (Original) The apparatus for etching a glass substrate of Claim 11, wherein said holder contains a plurality of glass substrates.

Claims 18 and 19 (Canceled).

20. (Original) The apparatus for etching a glass substrate of Claim 11, wherein said holder is located in an interior of said etching bath.

21. (Previously Presented) The apparatus for etching a glass substrate of Claim 11, further comprising a temperature sensor installed in said etching bath, wherein the temperature sensor monitors the temperature of the etching bath.